L Number	Hits	Search Text	DB	Time stamp
1	35	(spin-on or polyimide) with ("l-line photoresist" or	USPAT;	2003/04/04
		"ultra-violet photoresist" or anti-reflection)	US-PGPUB	11:54
2	5	"bottom anti-reflection" with (SiN or "silicon nitride")	USPAT;	2003/04/04
_			US-PGPUB	11:55
3	293	anti-reflection with (SiN or "silicon nitride")	USPAT; US-PGPUB	2003/04/04
	1001	400 /for 0== colo	EPO; JPO;	13:36 2003/04/04
4	1201	438/for.355.ccls.	DERWENT	13:36
_	273	438/for.489.ccls.	EPO; JPO;	2003/04/04
5	2/3	430/101.409.0018.	DERWENT	13:37
6	1672	damascene	EPO; JPO;	2003/04/04
·	10/=	aumustone .	DERWENT	13:37
7	o	438/for.355.ccls. and damascene	EPO; JPO;	2003/04/04
'		10-7000	DERWENT	13:37
8	О	438/for.489.ccls. and damascene	EPO; JPO;	2003/04/04
	_		DERWENT	13:37
<u>-</u>	528	438/631.ccls.	USPAT;	2003/04/03
	Ū		US-PGPUB	15:05
-	218279	plasma or "ultra-violet curing" or immersion	USPAT;	2003/04/03
	,,	ļ -	US-PGPUB	15:05
-	7838	"l-line photoresist" or "ultra-violet photoresist" or	USPAT;	2003/04/03
	, 5	anti-reflection	US-PGPUB	15:34
-	2203	(plasma or "ultra-violet curing" or immersion) and ("l-line	USPAT;	2003/04/03
İ	_	photoresist" or "ultra-violet photoresist" or anti-reflection)	US-PGPUB	15:16
-	8	438/631.ccls. and ((plasma or "ultra-violet curing" or	USPAT;	2003/04/03
		immersion) and ("l-line photoresist" or "ultra-violet	US-PGPUB	15:29
		photoresist" or anti-reflection))		
-	580	438/633.ccls.	USPAT;	2003/04/03
	-		US-PGPUB	15:29
-	17	((plasma or "ultra-violet curing" or immersion) and ("l-line	USPAT;	2003/04/03
		photoresist" or "ultra-violet photoresist" or anti-reflection))	US-PGPUB	15:29
		and 438/633.ccls.		
-	9927	"l-line photoresist" or "ultra-violet photoresist" or	USPAT;	2003/04/03
		anti-reflection or DUV or BARC	US-PGPUB	15:32
-	16	438/631.ccls. and ("l-line photoresist" or "ultra-violet	USPAT;	2003/04/03
		photoresist" or anti-reflection or DUV or BARC)	US-PGPUB	15:32
-	8	(438/631.ccls. and ("l-line photoresist" or "ultra-violet	USPAT;	2003/04/03
		photoresist" or anti-reflection or DUV or BARC)) not	US-PGPUB	15:34
		(438/631.ccls. and ((plasma or "ultra-violet curing" or		
		immersion) and ("l-line photoresist" or "ultra-violet	-	
		photoresist" or anti-reflection)))		
-	88327	(filling or fill or filled) with (opening or hole or via)	USPAT;	2003/04/03
			US-PGPUB	15:36
-	49	("l-line photoresist" or "ultra-violet photoresist" or	USPAT;	2003/04/03
		anti-reflection or DUV or BARC) with ((filling or fill or filled)	US-PGPUB	15:47
	_	with (opening or hole or via))	HODATE	0000/5:/==
-	298	438/634.ccls.	USPAT;	2003/04/03
		((1 1.3) 1.1 1.1 1.2 1.201.11	US-PGPUB	15:47
-	14	((plasma or "ultra-violet curing" or immersion) and ("l-line	USPAT;	2003/04/03
		photoresist" or "ultra-violet photoresist" or anti-reflection))	US-PGPUB	15:48
		and 438/634.ccls.	TIODATE.	0000/01/00
-	484	438/638.ccls.	USPAT;	2003/04/03
	_	((-1,,,,,,,,	US-PGPUB	15:48
-	20	((plasma or "ultra-violet curing" or immersion) and ("l-line	USPAT;	2003/04/03
		photoresist" or "ultra-violet photoresist" or anti-reflection))	US-PGPUB	15:49
		and 438/638.ccls.	HCDAT.	2000/04/00
-	371	(plasma or "ultra-violet curing" or immersion) and	USPAT;	2003/04/03
		438/631.ccls.	US-PGPUB USPAT;	15:49 2003/04/03
-	13	("I-line photoresist" or "ultra-violet photoresist" or	US-PGPUB	16:06
•		anti-reflection or DUV or BARC) and ((plasma or "ultra-violet	03-FGFUD	10.00
_	909-	curing" or immersion) and 438/631.ccls.)	USPAT;	2003/04/03
-	8387	(protective or cap) with (plasma or curing or immersion)	US-PGPUB	16:07
	580	438/633.ccls.	USPAT;	2003/04/03
_ '				

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, 			TTODAM	1
-	25		USPAT;	2003/04/03
		438/633.ccls.	US-PGPUB	16:16
-	20	438/638.ccls. and ((protective or cap) with (plasma or curing	USPAT;	2003/04/03
		or immersion))	US-PGPUB	16:18
-	0	("6316351,6100184").PN.	USPAT;	2003/04/03
			US-PGPUB	16:19
-	0	("6316351, 6100184").PN.	USPAT;	2003/04/03
			US-PGPUB	16:19
-	2	(("6316351") or ("6100184")).PN.	USPAT;	2003/04/03
			US-PGPUB	16:19
-	О	("(SiN or "silicon nitride") with 2").PN.	USPAT;	2003/04/03
			US-PGPUB	16:29
-	7960	(SiN or "silicon nitride") with (plasma or "ultra-violet curing"	USPAT;	2003/04/03
		or immersion)	US-PGPUB	16:31
-	76	438/633.ccls. and ((SiN or "silicon nitride") with (plasma or	USPAT;	2003/04/03
		"ultra-violet curing" or immersion))	US-PGPUB	16:30
-	0	protecitve with (SiN or "silicon nitride") with (plasma or	USPAT;	2003/04/03
		"ultra-violet curing" or immersion)	US-PGPUB	16:31
-	111	cap with (SiN or "silicon nitride") with (plasma or "ultra-violet	USPAT;	2003/04/03
		curing" or immersion)	US-PGPUB	16:31
-	4	438/633.ccls. and (cap with (SiN or "silicon nitride") with	USPAT;	2003/04/04
		(plasma or "ultra-violet curing" or immersion))	US-PGPUB	11:46